Docket No.: 4684-030

## JC10 Rec'd PCT/PTO 2 TO TEC 2005

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Confirmation No.

Kang-Ho AHN

U.S. Patent Application No.: -----

Group Art Unit: -----

Filed: herewith

For:

APPARATUS FOR CONTROLLING FLOW RATE OF GASES USED IN

SEMICONDUCTOR DEVICE BY DIFFERENTIAL PRESSURE

## PRELIMINARY AMENDMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Preliminary to examination of the above-referenced application, please amend the application as follows: